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WANG et al.(10) **Pub. No.: US 2016/0329395 A1**(43) **Pub. Date: Nov. 10, 2016**(54) **ARRAY SUBSTRATE, MANUFACTURE
METHOD THEREOF, DISPLAY DEVICE****Publication Classification**(71) Applicant: **BOE TECHNOLOGY GROUP CO.,
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LTD.**, Beijing (CN)(51) **Int. Cl.****H01L 27/32** (2006.01)**H01L 51/56** (2006.01)**H01L 51/00** (2006.01)**H01L 51/52** (2006.01)(52) **U.S. Cl.**CPC **H01L 27/3276** (2013.01); **H01L 51/5203**(2013.01); **H01L 27/3262** (2013.01); **H01L****27/3258** (2013.01); **H01L 51/56** (2013.01);**H01L 51/0021** (2013.01)(21) Appl. No.: **14/893,325**(22) PCT Filed: **Apr. 17, 2015**(86) PCT No.: **PCT/CN2015/076914**

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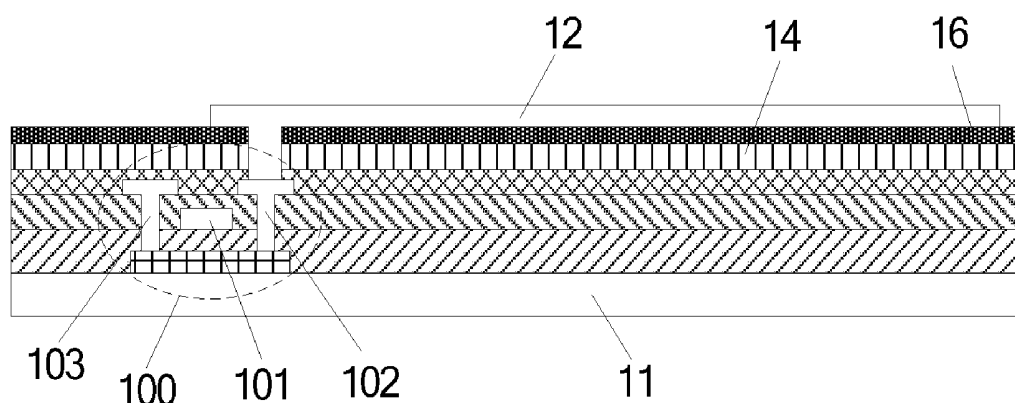
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Dec. 1, 2014 (CN) 201410720593.9

(57)

ABSTRACT

An array substrate, a manufacture method thereof, and a display device are provided. The array substrate includes a first electrode (12), a second electrode (15); a light-emitting functional layer (13) located between the first electrode (12) and the second electrode (15); and an organic planar layer (14). The first electrode (12) is formed on the organic planar layer (14). The first electrode (12) includes metal electrode or metal alloy electrode. An oxide conductive layer (16) is further formed between the organic planar layer (14) and the first electrode (12).



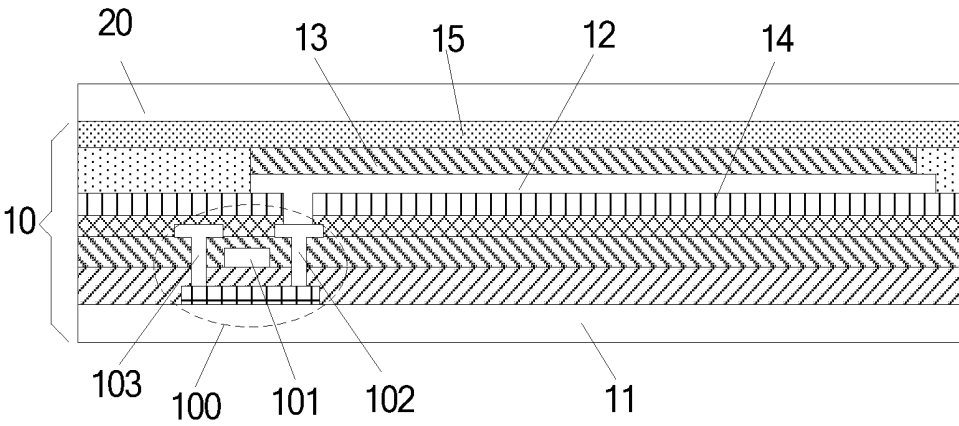


Fig. 1

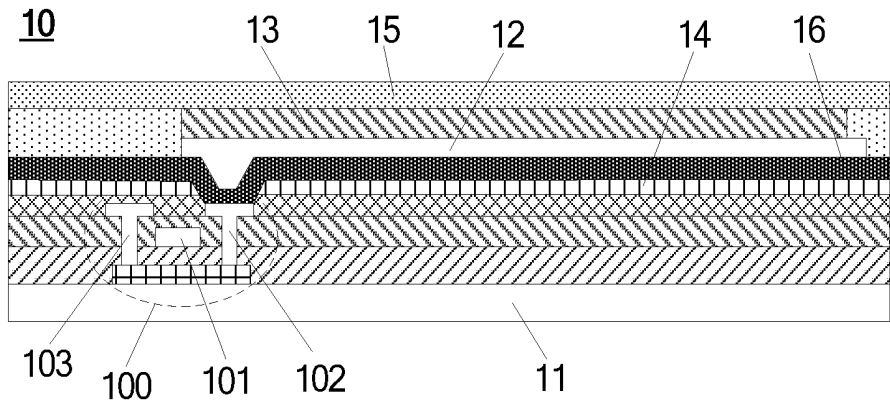


Fig. 2

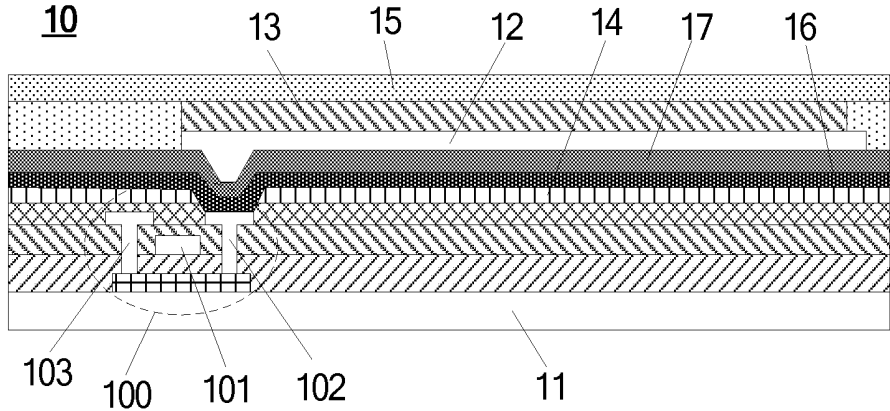


Fig. 3

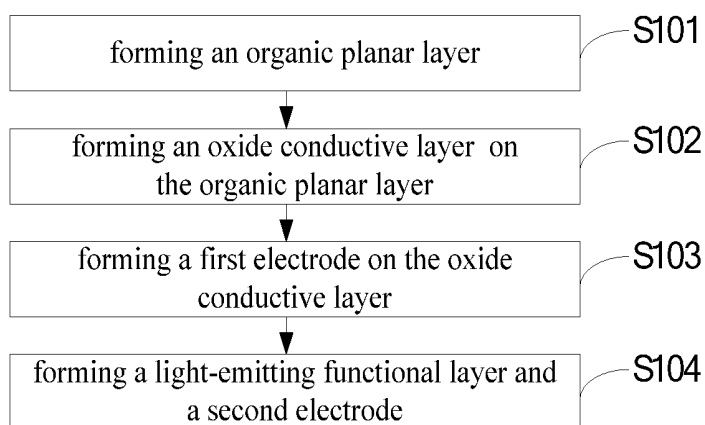


Fig. 4

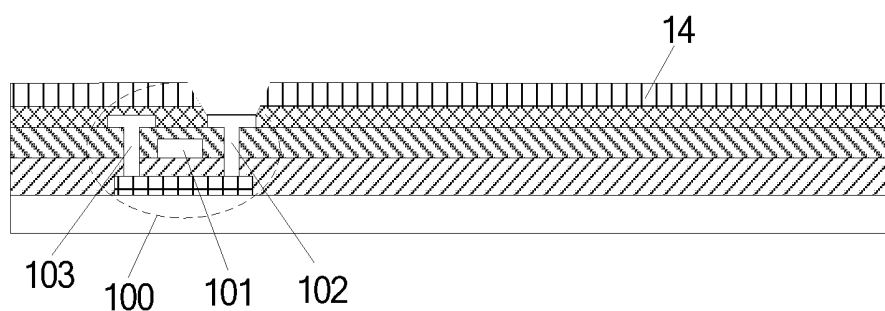


Fig. 5

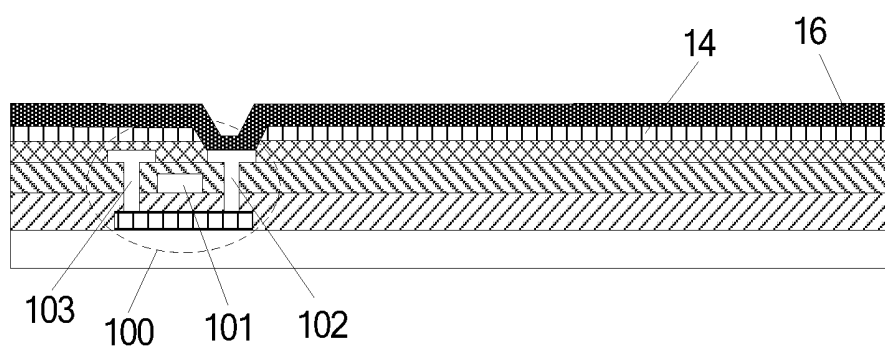


Fig. 6

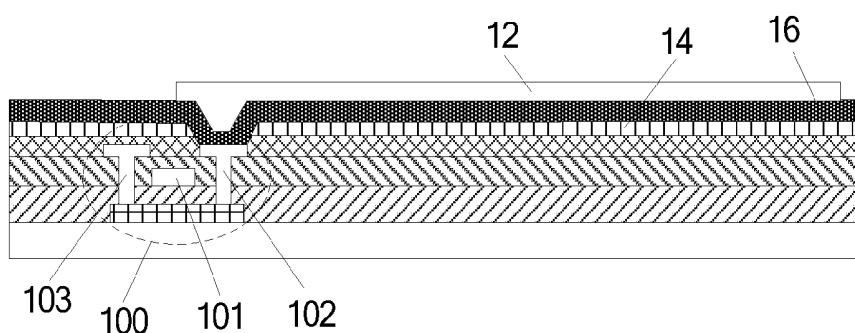


Fig. 7

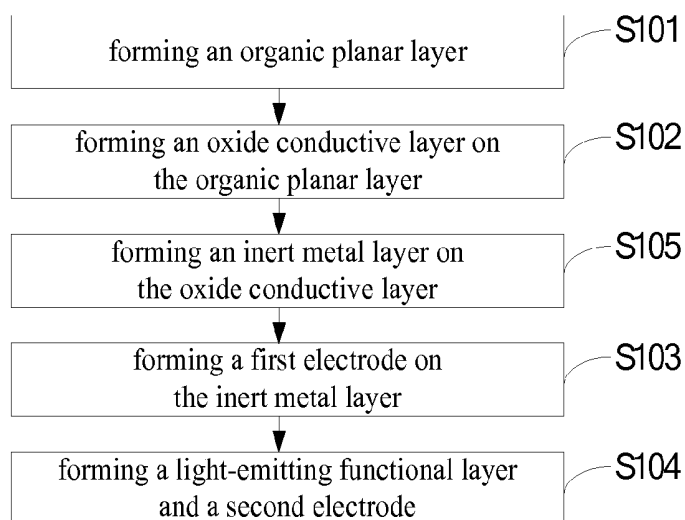


Fig. 8

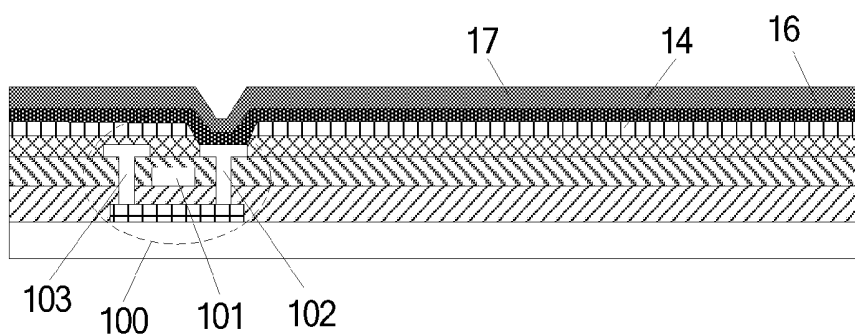


Fig. 9

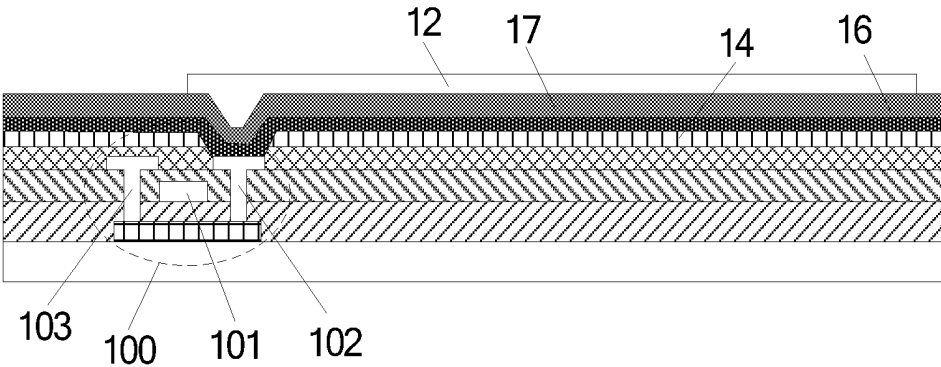


Fig. 10

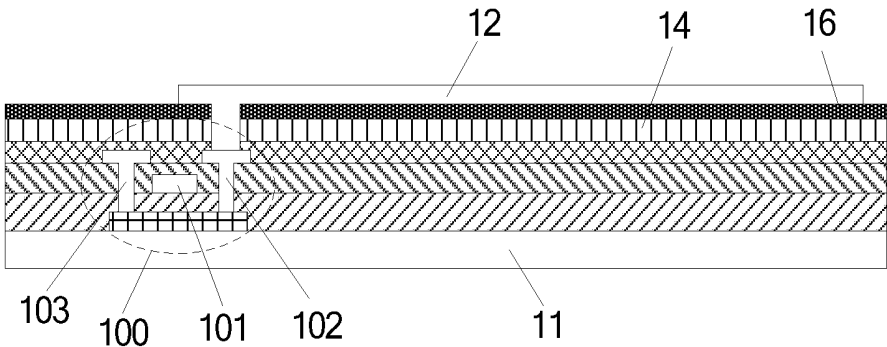


Fig. 11

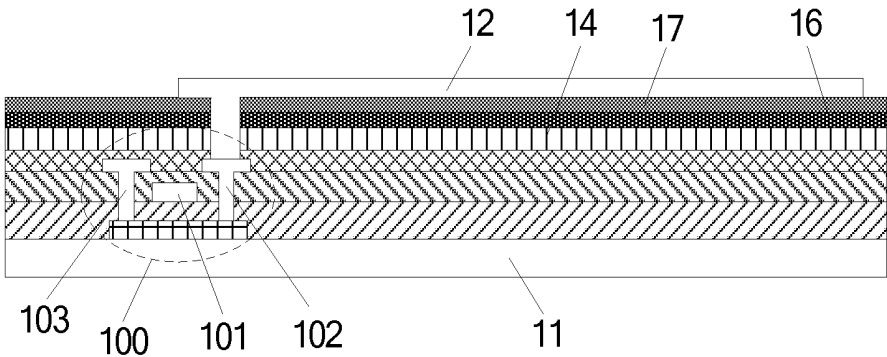


Fig. 12

ARRAY SUBSTRATE, MANUFACTURE METHOD THEREOF, DISPLAY DEVICE

TECHNICAL FIELD

[0001] Embodiments of the present invention relate to an array substrate, a manufacture method thereof, and a display device.

BACKGROUND

[0002] Organic light-emitting diode (OLED) display panels can achieve self-luminous display and are bendable and able to roll up for being formed by organic materials, and thus have been highly favored by users. The principle of the OLED display panel emitting light is in that organic materials are deposited between two electrodes, and the two electrodes will supply the organic materials with electric power so as to allow the organic materials to emit light.

SUMMARY

[0003] Embodiments of the present invention provide an array substrate, a manufacture method thereof, and a display device.

[0004] According to embodiments of the present invention, it provides an array substrate including a first electrode; a second electrode; a light-emitting functional layer located between the first electrode and the second electrode; and an organic planar layer, wherein the first electrode is formed on the organic planar layer, the first electrode includes metallic electrode or metal alloy electrode; and an oxide conductive layer is further formed between the organic planar layer and the first electrode.

[0005] Embodiments of the present invention provide a display device including any array substrate as provided by the embodiments of the present invention.

[0006] Embodiments of the present invention provide a manufacture method of array substrate, including: forming an organic planar layer; forming an oxide conductive layer on the organic planar layer; forming a first electrode on the oxide conductive layer; and forming a light-emitting functional layer and a second electrode.

BRIEF DESCRIPTION OF THE DRAWINGS

[0007] Embodiments of the present invention will be described in more detail below with reference to the accompanying drawings to enable an ordinary skill in the art to understand the present invention more clearly, wherein:

[0008] FIG. 1 is a schematic view illustrating an OLED display panel;

[0009] FIG. 2 is a schematic view illustrating an array substrate as provided by an embodiment of the present invention;

[0010] FIG. 3 is a schematic diagram illustrating another array substrate as provided by an embodiment of the present invention;

[0011] FIG. 4 is a schematic diagram illustrating a manufacture method of array substrate as provided by an embodiment of the present invention;

[0012] FIG. 5 is a schematic view illustrating a process of forming an organic planar layer as provided by an embodiment of the present invention;

[0013] FIG. 6 is a schematic view illustrating a process of forming an oxide conductive layer on an organic planar layer as provided by an embodiment of the present invention;

[0014] FIG. 7 is a schematic view illustrating a process of forming a first electrode on an oxide conductive layer as provided by an embodiment of the present invention;

[0015] FIG. 8 is a schematic diagram illustrating another manufacture method of array substrate as provided by an embodiment of the present invention;

[0016] FIG. 9 is a schematic view illustrating a process of forming an inert metal layer formed on an oxide conductive layer as provided by an embodiment of the present invention;

[0017] FIG. 10 is a schematic view illustrating a process of forming a first electrode on an inert metal layer as provided by an embodiment of the present invention;

[0018] FIG. 11 is a schematic view illustrating an electrical connection between a first electrode and a drain electrode as provided by an embodiment of the present invention; and

[0019] FIG. 12 is a schematic view illustrating another electrical connection between a first electrode and a drain electrode as provided by an embodiment of the present invention.

DETAILED DESCRIPTION

[0020] Technical solutions according to the embodiments of the present invention will be described clearly and completely as below in conjunction with the accompanying drawings of embodiments of the present invention. It is apparent that the described embodiments are only a part of but not all of exemplary embodiments of the present invention. Based on the described embodiments of the present invention, various other embodiments can be obtained by those of ordinary skill in the art without creative labor and those embodiments shall fall into the protection scope of the present invention.

[0021] Unless otherwise defined, all the technical and scientific terms used herein have the same meanings as commonly understood by one of ordinary skill in the art to which the present invention belongs. The terms, such as “first,” “second,” or the like, which are used in the description and the claims of the present application, are not intended to indicate any sequence, amount or importance, but for distinguishing various components. Also, the terms, such as “a/an,” “one,” or the like, are not intended to limit the amount, but for indicating the existence of at least one. The terms, such as “comprise/comprising,” “include/including,” or the like are intended to specify that the elements or the objects stated before these terms encompass the elements or the objects and equivalents thereof listed after these terms, but not preclude other elements or objects. The terms, “on,” “under,” or the like are only used to indicate relative position relationship, and when the position of the object which is described is changed, the relative position relationship may be changed accordingly. For example, as used in embodiments of the present invention, terms “on” and “under/below” are interpreted with reference to a sequence when films are formed, for example, a film defined as being on the other film is a film formed later with respect to the other film, and a film defined as being under/below the other film is a film formed previously with respect to the other film.

[0022] As illustrated in FIG. 1, an active matrix OLED display device includes an array substrate 10 and a package substrate 20 which are assembled with each other. The array substrate 10 has a substrate 11 provided with a plurality of driver thin film transistors (TFTs) 100 arranged in a matrix,

a first electrode **12**, a light-emitting functional layer (organic material) **13** and a second electrode **15** thereon. The driver TFT **100** includes a gate electrode **101**, a source electrode **103** and a drain electrode **102**. The drain electrode **102** of the driver TFT **100** is connected to the first electrode **12** and supplies the first electrode **12** with an electrical signal. The light-emitting functional layer **13** is formed between the second electrode **15** and the first electrode **12**, and upon the driver TFT **100** supplying the first electrode **12** with an electrical signal and meanwhile a circuit board supplying the second electrode **15** with an electrical signal through a transmission lead, current is passed between the first electrode **12** and the second electrode **15** so as to enable the light-emitting functional layer **13** emitting light for display.

[0023] The first electrode is a conductive electrode, and it is usually made of metal or metal alloy in order to reduce a resistance thereof. For example, the first electrode is made of Al—Nd alloy. As shown in FIG. 1, the array substrate **12** further includes an organic planar layer **14** made of organic material, and the first electrode **12** is formed on the organic planar layer **14**. However, the thermal coefficient of expansion of the organic planar layer is considerably different from that of a metal layer or metal alloy layer, and the metal layer or metal alloy layer has a poor adhesion to the organic planar layer. As a result, the metal layer or metal alloy layer is very likely to be separated from the organic planar layer due to a deformation of the metal layer or metal alloy layer caused by heating during the manufacture process of the display device or due to long term operation. As shown in FIG. 1, the first electrode **12** may be separated from the organic planar layer **14** as a result of becoming hot of the TFT **100** due to long term operation, which may further compromise the display quality.

[0024] Embodiments of the present invention provide an array substrate, including: a first electrode, a second electrode, and a light-emitting functional layer located between the first electrode and the second electrode. The array substrate further includes an organic planar layer, and the first electrode is formed on the organic planar layer. The first electrode is a metal electrode or a metal alloy electrode. An oxide conductive layer is further formed between the organic planar layer and the metal electrode or the metal alloy electrode.

[0025] It should be explained that the mentioned first electrode and second electrode can be a cathode or an anode, respectively. That is, when the first electrode is a cathode, the second electrode is an anode; or, when the second electrode is a cathode, the first electrode is an anode. The cathode and anode used herein is defined with respect to a current direction of the light-emitting functional layer, wherein the cathode serves to transmit electrons to the light-emitting functional layer and the anode serves to transmit holes to the light-emitting functional layer. For example, if the first electrode is a metal electrode or a metal alloy electrode, the second electrode can be a transparent electrode formed of Indium Tin Oxide (ITO) or the like.

[0026] The first electrode is formed on the organic planar layer, and the oxide conductive layer is formed between the first electrode and the organic planar layer; that is, an oxide conductive layer is further formed between the organic planar layer and the metal electrode or metal alloy electrode. The oxide conductive layer has good adhesion to both of the organic planar layer and the metal electrode or metal alloy electrode, and has a thermal coefficient of expansion with

less difference between that of the organic planar layer and the first electrode. As a result, the oxide conductive layer is hardly separated from the organic planar layer on which it is formed, and the metal electrode or metal alloy electrode is hardly to be separated from the oxide conductive layer on which it is formed. In addition, a lattice distortion of the oxide conductive layer is helpful for buffering and releasing a stress of the first electrode and the organic planar layer which are disposed adjacent to the oxide conductive layer. This is attributed to a reduced stress achieved by arranging a layer of structure in an intermediate state to reduce a difference in lattice match; such stress resulted from lattice mismatch due to direct contact between different crystalline structures is usually relatively larger and may result in contact issue. Furthermore, in this way, both of the first electrode and the organic planar layer are hardly to be separated from the oxide conductive layer. Embodiments of the present invention will be described in more details with Al used as the metal and Al-alloy electrode used as the metal alloy electrode, in an exemplary way.

[0027] As illustrated in FIG. 2, the array substrate **10** includes an organic planar layer **14** and a first electrode **12** formed on the organic planar layer **14**. For example, the first electrode **12** is Al electrode or Al-alloy electrode, and an oxide conductive layer **16** is further formed between the first electrode **12** and the organic planar layer **14**. It should be understood that the array substrate can further include a passivation layer, a pixel defining layer and the like, although embodiments of the present invention merely illustrate certain structures such as films or layers which are in connection with the inventive concept by way of example. As illustrated in FIG. 2, the oxide conductive layer **16** is in direct contact with the organic planar layer **14**, and the first electrode **12** is formed on the oxide conductive layer **16**. The first electrode **12** has good adhesion to the oxide conductive layer **16**, and the oxide conductive layer **16** also has good adhesion to the organic planar layer **14**, meanwhile a thermal coefficient of expansion of the oxide conductive layer **16** has less difference from that of both the organic planar layer **14** and the first electrode **12**. As a result, the structures of films or layers can be formed on the array substrate in a more stable way so that the first electrode **12** is also hardly to be separated from the oxide conductive layer **16** even under a long term use, and the display quality of the display panel when used is improved. On the other hand, due to the lattice distortion of the oxide conductive layer, it is helpful for buffering and releasing a stress of the adjacent metal electrode or metal alloy electrode and a stress of the adjacent organic planar layer. For example, when the first electrode is formed on the oxide conductive layer, the stress as generated during the forming process can be absorbed by the oxide conductive layer so that the first electrode is hardly to be separated from the oxide conductive layer.

[0028] Optionally, as illustrated in FIG. 3, an inert metal layer **17** is further formed between the oxide conductive layer **16** and the first electrode **12**. Optionally, a material forming the inert metal layer can be any one of Mo, Ti, Ta and Nb or a combination thereof. The metal alloy can be Al—Nd alloy or Al—B—Ni alloy. A content of Al in the Al—B—Ni alloy is 99.3%, a content of B in the Al—B—Ni alloy is 0.2%, and a content of Ni in the Al—B—Ni alloy is 0.5%. An electrode of active metal such as Al or metal alloy such as active Al alloy is easily oxidized. For display panels in long term use, oxygen atoms in the oxide conductive layer

may partly migrate to oxidize the metal electrode or metal alloy electrode to generate oxides, which increases a resistance of the first electrode so that an inert metal layer is formed between the oxide conductive layer and the first electrode. The inert metal layer has good stability and also good adhesion to both the oxide conductive layer and the first electrode, so it is advantageous in preventing the electrode of active metal or active metal alloy from being oxidized. In addition, forming an inert metal layer between the oxide conductive layer and the first electrode is equivalent to electrically connecting the oxide conductive layer, the inert metal layer and the first electrode in parallel, which facilitates further reducing the resistance of the first electrode and improving the display quality.

[0029] For example, it can also provide other metal materials with good stability, such as Au and Pt, between the oxide conductive layer and the first electrode. However, such metal is usually expensive and leads to high cost of the display panel. Embodiments of the present invention can provide a metal layer of Mo between the oxide conductive layer and the first electrode, for example.

[0030] Optionally, the oxide conductive layer can be Indium Tin Oxide (ITO) conductive layer, Indium Zinc Oxide (IZO) layer, Indium Tin Zinc Oxide (ITZO) layer or Indium Gallium Zinc Oxide (IGZO) layer, and can also be a combined structure of these material layers.

[0031] It should be understood that the active matrix OLED display panel includes an array substrate and a package substrate. The array substrate is provided with a plurality of TFTs arranged in a matrix, a first electrode, an organic light-emitting functional layer and a second electrode formed on the TFTs. The display panel in which the display side is adjacent to the package substrate is referred to as a top-emitting display panel, while the display panel in which the display side is adjacent to the array substrate is referred to as bottom-emitting display panel. The array substrate as provided by embodiments of the present invention can be applied to an active matrix display panel or an passive matrix display panel.

[0032] Optionally, as illustrated in FIG. 2 and FIG. 3, the array substrate 10 further includes a TFT 100 located below the organic planar layer 14. The TFT 100 includes a gate electrode 101, a source electrode 103 and a drain electrode 102. The organic planar layer 14 covers the TFT 100. The first electrode 12 is electrically connected to the drain electrode 102. The display panel is of top-emitting type. The second electrode 15 is a transparent conductive electrode. Also, as illustrated in FIG. 3, an inert metal layer 17 is formed between the oxide conductive layer 16 and the first electrode 12. That is, in the top-emitting display panel, the second electrode adjacent to the display side is a transparent conductive electrode, and the first electrode far away from the display side is a high-reflective electrode formed of metal or metal alloy.

[0033] The transparent conductive electrode can be formed by using ITO, IZO, ITZO or IGZO as provided by the embodiments of the present invention.

[0034] For example, the first electrode and the drain electrode can be electrically connected by any ways as below.

[0035] Optionally, as illustrated in FIG. 2, the organic planar layer 14 is formed with a via hole at a location corresponding to the drain electrode 102 of the TFT 100, and the first electrode 12 and the oxide conductive layer 16 are

electrically connected to the drain electrode 12 of the TFT 100 through the via hole. That is, the oxide conductive layer is electrically connected to the drain electrode by directly contacting there-with through the via hole. The first electrode is in direct contact with the oxide conductive layer and electrically connected to the drain electrode.

[0036] Alternatively, as illustrated in FIG. 11, the organic planar layer 14 and the oxide conductive layer 16 are formed with a via hole at a location corresponding to the drain electrode 102 of the TFT 100, and the first electrode 12 is electrically connected to the drain electrode 102 of the TFT 100 by directly contacting there-with through the via hole.

[0037] In a case where the array substrate further includes an inert metal layer, the first electrode and the drain electrode can be electrically connected by any ways as below.

[0038] Optionally, as illustrated in FIG. 10, the organic planar layer 14 is formed with a via hole at a location corresponding to the drain electrode 102 of the TFT 100, and the first electrode 12, the inert metal layer 17 and the oxide conductive layer 16 are electrically connected to the drain electrode 102 of the TFT 100 through the via hole.

[0039] Alternatively, the organic planar layer and the oxide conductive layer are formed with a via hole at a location corresponding to the drain electrode 102 of the TFT 100, and the first electrode and the inert metal layer are electrically connected to the drain electrode of the TFT through the via hole. That is, the via hole is formed in the organic planar layer and in the oxide conductive layer, and the inert metal layer is electrically connected to the drain electrode of the TFT by directly contacting there-with through the via hole. The first electrode is in direct contact with the inert metal layer and electrically connected to the drain electrode.

[0040] Alternatively, as illustrated in FIG. 12, the organic planar layer 14, the oxide conductive layer 16 and the inert metal layer 17 are formed with a via hole at a location corresponding to the drain electrode 102 of the TFT 100, and the first electrode 12 is electrically connected to the drain electrode 102 of the TFT 100 by directly contacting there-with through the via hole.

[0041] Embodiments of the present invention provide a display device including any array substrate as provided by embodiments of the present invention. The display device can be a display component such as OLED display and any product or assembly that includes the display component and possesses display function, such as television, digital camera, mobile phone and tablet computer.

[0042] Embodiments of the present invention provide a manufacture method of array substrate as illustrated in FIG. 4, which includes the following steps.

[0043] Step S101, forming an organic planar layer 14, as illustrated in FIG. 5.

[0044] Step S102, forming an oxide conductive layer 16 on the organic planar layer 14, as illustrated in FIG. 6. The material forming the oxide conductive layer can be any one of ITO, IZO, ITZO and IGZO, or a combination thereof.

[0045] Step S103, forming a first electrode 12 on the oxide conductive layer 16, as shown in FIG. 7. The first electrode can be formed of metal or metal alloy. For example, the metal is Al, and the metal alloy is an Al-alloy. For example, the Al-alloy can be an Al—Nd alloy or an Al—B—Ni alloy.

[0046] S104, forming a light-emitting functional layer 13 and a second electrode 15, as shown in FIG. 2.

[0047] Alternatively, as illustrated in FIG. 8, it can further include a step between step S102 and S103 as below.

[0048] Step S105, forming an inert metal layer 17 on the oxide conductive layer 16, as shown in FIG. 9. For example, the material forming the inert metal layer can be any one of Mo, Ti, Ta and Nb, or a combination thereof.

[0049] As shown in FIG. 10, the above-mentioned step S103 can include: forming a first electrode 12 on the inert metal layer 17. FIG. 3 shows the array substrate after the light-emitting functional layer 13 and the second electrode 15 formed on the first electrode 12.

[0050] Optionally, before the above-mentioned step S101, the method further includes forming a TFT, as illustrated in FIGS. 5-7 and FIGS. 9-10, forming the TFT 100 includes forming a gate electrode 101, a source electrode 103 and a drain electrode 102. In a case where the display panel is a top-emitting display panel, the organic planar layer 14 covers the TFT 100, the first electrode 12 is electrically connected to the drain electrode 102, and the second electrode 15 is a transparent conductive electrode.

[0051] It should be understood that the first electrode is electrically connected to the drain electrode, for example, through a via hole. The first electrode can be electrically connected to the drain electrode through the via hole by any ways as below.

[0052] Optionally, the above-mentioned step S102 includes: forming a via hole in the organic planar layer 14 at a location corresponding to the drain electrode 102, as shown in FIG. 5. Forming the via hole in the organic planar layer can be performed after forming the organic planar layer, and can also be performed at the location corresponding to the drain electrode at the same time of forming the organic planar layer.

[0053] As shown in FIG. 6 and FIG. 7, the oxide conductive layer 16 formed on the organic planar layer 14 covers the via hole (i.e., the drain electrode 102), and the first electrode 12 as formed is electrically connected to the drain electrode 102 through the oxide conductive layer 16. Alternatively, as shown in FIG. 9 and FIG. 10, on the oxide conductive layer 16, it's further formed with an inert metal layer 17 which covers an area corresponding to the drain electrode 102, and the first electrode 12 as formed is electrically connected to the drain electrode 102 through the oxide conductive layer 16 and the inert metal layer 17.

[0054] Alternatively, as shown in FIG. 11, before forming the first electrode 12, the method further includes: forming a via hole in the organic planar layer 14 and in the oxide conductive layer 16 at a location corresponding to the drain electrode 102, and the first electrode 12 is directly electrically connected to the drain electrode 102 through the above-mentioned via hole.

[0055] Further optionally, as shown in FIG. 12, before forming the first electrode 12, the method further includes: forming a via hole in the organic layer 14, in the oxide conductive layer 16 and in the inert metal layer 17 at a location corresponding to the drain electrode 102, and the first electrode 12 is directly electrically connected to the drain electrode 102 through the above-mentioned via hole.

[0056] Further optionally, before forming the inert metal layer on the oxide conductive layer, the method further includes: forming a via hole in the organic planar layer and in the oxide conductive layer at a location corresponding to the drain electrode of the TFT, then the first electrode and the inert metal layer are electrically connected to the drain

electrode of the TFT through the via hole. That is, forming the via hole in the organic planar layer and in the oxide conductive layer. The inert metal layer is electrically connected to the drain electrode of the TFT by directly contacting there-with through the via hole. The first electrode is in direct contact with the inert metal layer and electrically connected to the drain electrode.

[0057] The via hole can be formed in various ways. For example, the via hole can be simultaneously formed in the organic planar layer and in the oxide conductive layer at the location corresponding to the drain electrode of the TFT after forming the organic planar layer and the oxide conductive layer; and it can also be formed by forming the organic planar layer and a via hole in the organic planar layer at the location corresponding to the drain electrode, and then forming the oxide conductive layer and the via hole at the location corresponding to the drain electrode.

[0058] The embodiments of the present invention provide an array substrate, a manufacture method thereof and a display device. The array substrate includes a first electrode; a second electrode; a light-emitting functional layer located between the first electrode and the second electrode; and an organic planar layer. The first electrode is formed on the organic planar layer. The first electrode includes metal electrode or metal alloy electrode. An oxide conductive layer is further formed between the organic planar layer and the metal electrode or metal alloy electrode. The oxide conductive layer has a good adhesion to both of the organic planar layer and the metal or metal alloy electrode, and it also has a thermal coefficient of expansion with less difference from that of both of the organic planar layer and the first electrode, as a result, both of the oxide conductive layer formed on the organic planar layer and the metal or metal alloy electrode formed on the oxide conductive layer are hardly to be separated. In addition, the lattice deformation of the oxide conductive layer is helpful for buffering and releasing the stress of the first electrode and the organic planar layer which are disposed adjacent to the oxide conductive layer, which also allows both the first electrode and the organic planar layer being hardly to be separated from the oxide conductive layer.

[0059] It is understood that the described above are just exemplary implementations of the present invention and the invention is not intended to be limited thereto. An ordinary skill in the art can make various variations and modifications to the present invention without departure from the spirit and the scope of the present invention, and such variations and modifications shall fall in the scope of the present invention. The scope of the present invention is defined by the claims.

[0060] The present application claims the priority of Chinese patent application No. 201410720593.9 filed on Dec. 1, 2014, and entitled "ARRAY SUBSTRATE, MANUFACTURE METHOD THEREOF, DISPLAY DEVICE", which is incorporated herein by reference entirely.

1. An array substrate, comprising:
 - a first electrode;
 - a second electrode;
 - a light-emitting functional layer located between the first electrode and the second electrode; and
 - an organic planar layer;
 wherein the first electrode is formed on the organic planar layer, and the first electrode is a metal electrode or metal alloy electrode; and

an oxide conductive layer is further formed between the organic planar layer and the first electrode.

2. The array substrate according to claim 1, wherein an inert metal layer is further formed between the oxide conductive layer and the first electrode.

3. The array substrate of claim 2, wherein material forming the inert metal layer comprises any one of Mo, Ti, Ta and Nb or a combination thereof.

4. The array substrate according to claim 1, wherein material forming the oxide conductive layer comprises any one of ITO, IZO, ITZO and IGZO, or a combination thereof.

5. The array substrate according to claim 1, wherein the metal comprises Al and the metal alloy comprises an Al-alloy.

6. The array substrate according to claim 5, wherein the Al-alloy comprises an Al—Nd alloy or an Al—B—Ni alloy.

7. The array substrate according to claim 1, further comprising a thin film transistor (TFT) located below the organic planar layer;

wherein, the organic planar layer is formed with a via hole at a location corresponding to a drain electrode of the TFT, the first electrode and the oxide conductive layer are electrically connected to the drain electrode of the TFT through the via hole; or,

the organic planar layer and the oxide conductive layer are formed with a via hole at a location corresponding to the drain electrode of the TFT, and the first electrode is electrically connected to the drain electrode of the TFT by directly contacting there-with through the via hole.

8. The array substrate according to claim 2, further comprising a thin film transistor (TFT) located below the organic planar layer;

wherein the organic planar layer is formed with a via hole at a location corresponding to a drain electrode of the TFT, and the first electrode, the inert metal layer and the oxide conductive layer are electrically connected to the drain electrode of the TFT through the via hole; or,

the organic planar layer and the oxide conductive layer are formed with a via hole at a location corresponding to the drain electrode of the TFT, and the first electrode and the inert metal layer are electrically connected to the drain electrode of the TFT through the via hole; or,

the organic planar layer, the oxide conductive layer and the inert metal layer are formed with a via hole at a location corresponding to the drain electrode of the TFT, and the first electrode is electrically connected to the drain electrode of the TFT by directly contacting there-with through the via hole.

9. A display device, comprising the array substrate of claim 1.

10. A manufacture method of array substrate, comprising: forming an organic planar layer;

forming an oxide conductive layer on the organic planar layer;

forming a first electrode on the oxide conductive layer, wherein the first electrode is a metal electrode or metal alloy electrode; and

forming a light-emitting functional layer and a second electrode.

11. The manufacture method according to claim 10, further comprising, after forming the oxide conductive layer on the organic planar layer and before forming the first electrode on the oxide conductive layer, forming an inert metal layer on the oxide conductive layer.

12. The manufacture method according to claim 11, wherein the first electrode is formed on the inert metal layer.

13. The manufacture method according to claim 10, further comprising, before forming the organic planar layer, forming a thin film transistor (TFT);

wherein the forming of the organic planar layer comprises: forming a via hole in the organic planar layer at a location corresponding to a drain electrode of the TFT to allow the first electrode and the oxide conductive layer being electrically connected to the drain electrode of the TFT through the via hole; or,

the method further comprising: before forming the first electrode, forming a via hole in the organic planar layer and in the oxide conductive layer at a location corresponding to the drain electrode of the TFT to allow the first electrode being electrically connected to the drain electrode of the TFT by directly contacting there-with through the via hole.

14. The manufacture method according to claim 11, further comprising: before forming the organic planar layer, forming a TFT;

wherein the forming of the organic planar layer comprises: forming a via hole in the organic planar layer at a location corresponding to a drain electrode of the TFT to allow the first electrode, the inert metal layer and the oxide conductive layer being electrically connected to the drain electrode of the TFT through the via hole; or,

the method further comprising: before forming the inert metal layer on the oxide conductive layer, forming a via hole in the organic planar layer and in the oxide conductive layer at a location corresponding to the drain electrode of the TFT to allow the first electrode and the inert metal layer being electrically connected to the drain electrode of the TFT through the via hole; or

the method further comprising: before forming the first electrode, forming a via hole in the organic planar layer, in the oxide conductive layer and in the inert metal layer at a location corresponding to the drain electrode of the TFT to allow the first electrode being electrically connected to the drain electrode of the TFT by directly contacting there-with through the via hole.

15. The manufacture method according to claim 11, wherein the material forming the inert metal layer comprises any one of Mo, Ti, Ta and Nb, or a combination thereof.

16. The manufacture method according to claim 10, wherein the material forming the oxide conductive layer comprises any one of ITO, IZO, ITZO and IGZO, or a combination thereof.

17. The manufacture method according to claim 10, wherein the metal is Al and the metal alloy is an Al-alloy.

18. The manufacture method according to claim 16, wherein the Al-alloy is an Al—Nd alloy or an Al—B—Ni alloy.

19. The array substrate according to claim 3, further comprising a thin film transistor (TFT) located below the organic planar layer;

wherein the organic planar layer is formed with a via hole at a location corresponding to a drain electrode of the TFT, and the first electrode, the inert metal layer and the oxide conductive layer are electrically connected to the drain electrode of the TFT through the via hole; or, the organic planar layer and the oxide conductive layer are formed with a via hole at a location corresponding to the drain electrode of the TFT, and the first electrode

and the inert metal layer are electrically connected to the drain electrode of the TFT through the via hole; or, the organic planar layer, the oxide conductive layer and the inert metal layer are formed with a via hole at a location corresponding to the drain electrode of the TFT, and the first electrode is electrically connected to the drain electrode of the TFT by directly contacting there-with through the via hole.

20. The array substrate according to claim 4, further comprising a thin film transistor (TFT) located below the organic planar layer;

wherein, the organic planar layer is formed with a via hole at a location corresponding to a drain electrode of the TFT, the first electrode and the oxide conductive layer are electrically connected to the drain electrode of the TFT through the via hole; or,

the organic planar layer and the oxide conductive layer are formed with a via hole at a location corresponding to the drain electrode of the TFT, and the first electrode is electrically connected to the drain electrode of the TFT by directly contacting there-with through the via hole.

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专利名称(译)	阵列基板，其制造方法，显示装置		
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申请(专利权)人(译)	京东方科技集团股份有限公司.		
当前申请(专利权)人(译)	京东方科技集团股份有限公司.		
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摘要(译)

提供一种阵列基板及其制造方法和显示装置。阵列基板包括第一电极（12），第二电极（15）；位于第一电极（12）和第二电极（15）之间的发光功能层（13）；和有机平面层（14）。在有机平面层（14）上形成第一电极（12）。第一电极（12）包括金属电极或金属合金电极。在有机平面层（14）和第一电极（12）之间进一步形成氧化物导电层（16）。

